

FORM PTO 1449 (modified) U. S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary) Submitted to the PTO: November 30, 2007				ATTY DOCKET NO. 03500.017774		APPLICATION NO 10/535,452	
				APPLICANTS MIKI OGAWA, ET AL.			
				FILING DATE May 19, 2005		GROUP 1765	
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		5,244,828	09/1993	Okada, et al.	437	81	
		5,240,558	08/1993	Kawasaki, et al.	156	659.1	
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		6,602,620	08/2003	Kikitsu, et al.	428	694 T	
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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
		5-55545	03/1993	Japan			Abstract
		0 851 506	07/1998	Europe			
		11-31862	02/1999	Japan			Abstract
		11-251334	09/1999	Japan			Abstract
		58-142523	08/1983	Japan			Abstract
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		M. Jacobs, et al., "Unbalanced Magnetron Sputtered Si-Al Coatings: Plasma Conditions and Film Properties Versus Sample Bias Voltage", Surface and Coatings Technology, 116-119, pp. 735-741 (1999).					
		C.D. Adams, et al., "Transition from Lateral to Transverse Phase Separation During Film Co-Deposition", Appl. Phys. Lett., 59 (20), pp. 2535-2537 (November 11, 1991).					
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EXAMINER				DATE CONSIDERED			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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		2004/0048092	03/2004	Yasui, et al.	428	642	
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		WO 01/71394	09/2001	PCT			No
		2000-327491	11/2000	Japan			Abstract
		2-139714	05/1990	Japan			Abstract
		WO 03/069677	08/2003	PCT			
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